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Client Reference: P-0166.010-US

**REPLY UNDER 37 C.F.R. §1.116
EXPEDITED PROCEDURE
TECHNOLOGY CENTER ART UNIT 2882**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re PATENT APPLICATION of:
CASTENMILLER et al.

Confirmation Number: 4742

Application No.: 09/739,622

Group Art Unit: 2882

Filed: December 20, 2000

Examiner: Ho, Allen

Title: POSITION MEASURING SYSTEM FOR USE IN LITHOGRAPHIC APPARATUS
(As Amended)

AMENDMENT AFTER FINAL REJECTION UNDER 37 C.F.R. §1.116

Mail Stop Amendment After Final
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

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APR 13 2004

Technology Center 2800

Sir:

In response to the Office Action dated January 30, 2004, please amend the above-identified application as follows:

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently amended) A lithographic projection apparatus comprising:
 - a projection beam illumination system which supplies a projection beam of radiation;
 - a first object table for holding a protection beam patterning device which patterns the projection beam according to a desired pattern;
 - a second object table for holding a substrate; and
 - a projection system which images the patterned beam onto a target portion of the substrate;
 - a reference frame; and